

DESCRIPTION

TITLE OF THE INVENTION: LIQUID CHEMICAL PROCESSING DEVICE

TECHNICAL FIELD

5 [0001]

The present invention relates to a liquid chemical processing device.

BACKGROUND ART

10 [0002]

Conventionally, there are liquid chemical processing devices that immerse substrates in a stripping solution so as to strip off resists or metal films formed on the substrates.

15 [0003]

Patent Document 1 discloses a liquid chemical processing device in which a holder horizontally holds substrates and a nozzle disposed near a side surface of the holder ejects a stripping solution to an upper side and a lower side of the substrates to prevent a stripped resist or a stripped metal film from readhering to the substrates.

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PRIOR ART DOCUMENT

PATENT DOCUMENT

25 [0004]

SUMMARY OF THE INVENTION

PROBLEMS TO BE SOLVED BY THE INVENTION

5 [0005]

In Patent Document 1, stripping processing is performed by a batch method in which a group of substrates is immersed in a stripping solution in a horizontal posture. Processing is repeatedly performed in which the group of
10 substrates immersed in the stripping solution is lifted up, one substrate is taken out from the group of substrates and replaced with another substrate in an empty portion, and then the group of substrates is immersed. In the stripping processing performed by the batch method, each of the
15 substrates is immersed and lifted up individually, and hence it is difficult to manage immersion temperature and immersion time for the individual substrates. Accordingly, variation occurs in resist removal for each substrate, which affects quality in a subsequent step.

20 [0006]

It is therefore an object of the present invention to provide a liquid chemical processing device that reduces variation in resist removal for each substrate.

25 MEANS FOR SOLVING THE PROBLEMS

[0007]

In order to solve the above problems, a liquid chemical processing device according to one aspect of the present invention includes:

5 a processing tank in which resist removal processing is performed by immersing substrates in a chemical;

 a plurality of holders configured to hold the substrates in a vertical posture;

10 vertical drivers configured to individually and vertically drive the holders; and

 a chuck configured to disengageably chuck the substrates,

 wherein the vertical drivers are configured to
15 individually and vertically move the holders between an immersed position where the substrates are immersed in the chemical and a non-immersed position where the substrates are lifted up from the chemical, and the substrates held by the holders are subjected to the resist removal processing
20 in a single wafer manner.

[0008]

In this specification, the term "resist removal processing" includes not only processing of removing a resist alone but also processing of removing a resist and a metal
25 film provided on the resist together, so-called lift-off

processing.

EFFECTS OF THE INVENTION

[0009]

5 According to the present invention, each of the substrates held by the holders is subjected to the resist removal processing in a single wafer manner by being individually and vertically moved between the immersed position and the non-immersed position. Accordingly, it is
10 possible to reduce variation in resist removal for each substrate.

BRIEF DESCRIPTION OF THE DRAWINGS

[0010]

15 FIG. 1 is a plan view illustrating a liquid chemical processing device according to a first embodiment.

 FIG. 2 is a schematic diagram illustrating a swelling processing system in the liquid chemical processing device illustrated in FIG. 1.

20 FIG. 3 is a schematic diagram illustrating resist removal processing in the liquid chemical processing device illustrated in FIG. 1.

 FIG. 4 is a schematic front view illustrating a vertical driver in the liquid chemical processing device
25 illustrated in FIG. 1.

FIG. 5 is a schematic side view of the vertical driver illustrated in FIG. 4.

FIG. 6 is a schematic front view illustrating a chuck in the liquid chemical processing device illustrated in FIG. 1.

FIG. 7 is a schematic side view of the chuck illustrated in FIG. 6.

FIG. 8 is a plan view illustrating a swelling processing tank in the liquid chemical processing device illustrated in FIG. 1.

FIG. 9 is a plan view illustrating a swelling processing tank in a liquid chemical processing device according to a second embodiment.

FIG. 10 is a plan view illustrating a liquid chemical processing device according to a third embodiment.

FIG. 11 is a plan view illustrating a swelling processing tank in the liquid chemical processing device illustrated in FIG. 10.

FIG. 12 is a plan view illustrating a swelling processing tank in a liquid chemical processing device according to a fourth embodiment.

MODES FOR CARRYING OUT THE INVENTION

[0011]

Hereinafter, embodiments of a liquid chemical

processing device 1 according to the present invention will be described with reference to the drawings.

[0012]

[First embodiment]

5 A liquid chemical processing device 1 according to a first embodiment will be described with reference to FIGS. 1 to 6. FIG. 1 is a plan view illustrating the liquid chemical processing device 1 according to the first embodiment. FIG. 2 is a schematic diagram illustrating a swelling processing system 3 in the liquid chemical processing device 1 illustrated in FIG. 1. FIG. 3 is a schematic diagram illustrating resist removal processing in the liquid chemical processing device 1 illustrated in FIG. 1. FIG. 4 is a schematic front view illustrating a vertical driver 20 in the liquid chemical processing device 1 illustrated in FIG. 1. FIG. 5 is a schematic side view of the vertical driver 20 illustrated in FIG. 4. FIG. 6 is a schematic front view illustrating a chuck 55 in the liquid chemical processing device 1 illustrated in FIG. 1. FIG. 7 is a schematic side view of the chuck 55 illustrated in FIG. 6. FIG. 8 is a plan view illustrating a swelling processing tank 10 in the liquid chemical processing device 1 illustrated in FIG. 1.

[0013]

25 As illustrated in FIG. 1, the liquid chemical

processing device 1 includes the swelling processing tank 10, cleaning processing tanks 5, 5, drying processing tanks 7, 7, a controller 8, and an articulated robot 9. The articulated robot 9 includes a dry-dedicated robot and a wet-dedicated robot. In the liquid chemical processing device 1 illustrated in FIG. 1, one cleaning processing tank 5 and one drying processing tank 7 are disposed on one side with respect to the swelling processing tank 10, and another cleaning processing tank 5 and another drying processing tank 7 are disposed on the other side with respect to the swelling processing tank 10. In addition, carriers 2, 2 are disposed on an opposite side with respect to the swelling processing tank 10, the cleaning processing tanks 5 and the drying processing tanks 7 being interposed therebetween. The swelling processing tank 10, the cleaning processing tanks 5, 5, the drying processing tanks 7, 7, and the carriers 2, 2 are arranged to surround the articulated robot 9 in a plan view. An object of the liquid chemical processing device 1 is to make circuit patterns or the like on flat substrates 4 (for example, wafers) by removing photoresists and metal films formed thereon, except for the circuit patterns, from the substrates 4 (hereinafter, photoresists and metal films are collectively referred to as "coating material").

[0014]

As illustrated in FIG. 2, the swelling processing system 3 includes the swelling processing tank 10, a plurality of substrate up-and-down actuators 20, and a sludge recovery tank 30. As will be described later, in the swelling processing system 3, the plurality of substrate up-and-down actuators 20 disposed in the swelling processing tank 10 are configured to perform resist removal processing on a plurality of substrates 4 in a single wafer manner.

[0015]

The swelling processing tank 10 stores a stripping solution (that is, chemical (liquid chemical)) 6 and includes a processing tank 10a, a storage tank 10b, and a discharge tank 10c. The swelling processing tank 10 is configured such that the stripping solution (chemical) 6 flows from the processing tank 10a to the storage tank 10b, and further flows from the storage tank 10b to the discharge tank 10c. That is, the stripping solution 6 flows in one direction in the swelling processing tank 10.

[0016]

As illustrated in FIGS. 1 and 8, in the processing tank 10a, the plurality of substrate up-and-down actuators 20 are arranged in a row spaced apart from each other along a longitudinal direction (that is, lateral direction) of the processing tank 10a. Nozzles 14 are each disposed between two adjacent substrate up-and-down

actuators 20. Also, two nozzles 14 are each disposed adjacent and outwardly to two substrate up-and-down actuators 20 at one end and another end. The controller 8 individually controls each of the substrate up-and-down actuators 20.

[0017]

The controller 8 includes a central processing unit (CPU), and controls various operations and processes in the liquid chemical processing device 1 using various memories such as read only memories (ROMs) and random access memories (RAMs), and various input devices and output devices. Details of the substrate up-and-down actuator 20 and the articulated robot 9 will be described later.

[0018]

In the processing tank 10a, the substrate up-and-down actuator 20 is configured to move the substrate 4 in a vertical direction between an immersed position where the substrate 4 is immersed in the stripping solution 6 and a non-immersed position where the substrate 4 is lifted up from the stripping solution 6. By immersing the substrate 4 in the stripping solution (chemical) 6 stored in the processing tank 10a, a photoresist formed on the substrate 4 swells, and the coating material is stripped off from the substrate 4.

[0019]

As illustrated in FIG. 2, a bottom of the swelling processing tank 10 is inclined downward with respect to a flow direction of the stripping solution (chemical) 6 from the processing tank 10a to the discharge tank 10c. An ultrasonic generator 17 is disposed at the bottom of the swelling processing tank 10 (specifically, a bottom of the processing tank 10a and a bottom of the storage tank 10b). With such a configuration including the ultrasonic generator 17, stripping of the coating material from the substrates 4 is promoted, and the coating material stripped off from the substrates 4 is pulverized, so that sludge generated by the pulverization easily flows downstream.

[0020]

The nozzles 14 are disposed at an upper portion and upstream side of the processing tank 10a. The nozzles 14 are configured to eject the stripping solution (that is, chemical) 6 downward and obliquely toward the center of the substrate 4 to generate a downflow. With such a configuration, the stripped coating material is prevented from readhering to the substrates 4, so that the generated sludge is easily recovered. The nozzles 14 are, for example, full cone nozzles. For example, flow rates of the stripping solution (that is, chemical) 6 ejected from the nozzles 14 are 1 to 2 liters/minute, and a flow velocity of the stripping solution (that is, chemical) 6 is 1 to 1.8 m/second.

[0021]

The processing tank 10a and the storage tank 10b are separated from each other by a communication side-wall 11. The processing tank 10a communicates with the storage tank 10b adjacent to the processing tank 10a through a communication port 15 provided in a bottom of the communication side-wall 11. With such a configuration, the stripping solution (chemical) 6 in the processing tank 10a flows into the storage tank 10b as a downflow. Accordingly, it is possible to prevent the stripped coating material from readhering to the substrates 4. The storage tank 10b and the discharge tank 10c adjacent to the storage tank 10b are also separated from each other by an overflow side-wall 12.

[0022]

In the storage tank 10b, a stagnation prevention portion 16 is formed at a corner, on a bottom, on an opposite side of the communication port 15 (that is, a side of the overflow side-wall 12). With such a configuration, it is possible to prevent sludge from accumulating at the corner where the bottom of the storage tank 10b and the overflow side-wall 12 intersect with each other. The stagnation prevention portion 16 has a round shape or a chamfered shape.

[0023]

A height of the overflow side-wall 12 is set to be lower than a height of the communication side-wall 11.

As a result, the stripping solution (that is, chemical) 6 in the storage tank 10b that flows over the overflow side-wall 12 flows into the discharge tank 10c..

[0024]

5 A circulation path 40 through which the stripping solution (that is, chemical) 6 flows and circulates in the swelling processing system 3 will be described with reference to FIG. 2. A pipe 41 is connected to a bottom of the discharge tank 10c. A valve 46 provided in a middle of
10 the pipe 41 controls a flow of the stripping solution (that is, chemical) 6 through the circulation path 40.

[0025]

 The pipe 41 is connected to an upper portion of the sludge recovery tank 30. The sludge recovery tank 30
15 includes a mesh filter 31, which is made of stainless steel, in an upper portion thereof. The mesh filter 31 is disposed just below a connection portion of the pipe 41 so as to receive the stripping solution (that is, chemical) 6 that flows through the pipe 41. The mesh filter 31 includes, for
20 example, a coarse mesh basket 32 coarser than 20 mesh (that is, mesh opening of 0.77 to 0.98 mm), an intermediate mesh basket 33 that is substantially 50 mesh (that is, mesh opening of 0.28 to 0.33 mm), and a fine mesh basket 34 that is substantially 100 mesh (that is, mesh opening of 0.15 mm).
25 The mesh filter 31 is configured to be attached to and

detached from the sludge recovery tank 30 through a filter take-out portion 36. An exhaust unit 37 opened to an atmosphere is provided in the upper portion of the sludge recovery tank 30.

5 [0026]

A circulation pump 47 is connected to the downstream side of the sludge recovery tank 30 via a pipe 42. A liquid cyclone 48 is connected to the downstream side of the circulation pump 47 via a pipe 43. A chemical filter
10 49 is connected to the downstream side of the liquid cyclone 48 via a pipe 44. The nozzles 14 are connected to the downstream side of the chemical filter 49 via a pipe 45. Therefore, in the swelling processing system 3, the stripping solution (chemical) 6 circulates between the discharge tank
15 10c and the nozzles 14 disposed in the processing tank 10a through the circulation path 40. By circulating the stripping solution (chemical) 6, an organic solvent and metal contained in the used stripping solution (chemical) 6 can be reused, so that running costs of the liquid chemical
20 processing device 1 can be reduced.

[0027]

The circulation path 40 of the swelling processing system 3 is provided with filtering systems 31, 48, and 49 in which recovery target size of the sludge
25 contained in the stripping solution (chemical) 6 is reduced

stepwise (for example, in three stages). That is, the mesh filter 31 serves as first-stage filtering to filter sludge of 100 μm or more. The liquid cyclone 48 serves as second-stage filtering to filter sludge of 2 μm to 100 μm by performing solid-liquid separation by centrifugal force. The chemical filter 49 serves as third-stage filtering to filter sludge of 0.2 μm to 2 μm . With such a configuration, it is possible to reduce replacement frequency of expensive filter elements, suppress downtime of the liquid chemical processing device 1, and increase production efficiency.

[0028]

The substrate up-and-down actuator 20 serves as a vertical driver, and includes a vertical movement arm 21, a holder 22, substrate receivers 23, and a vertical movement actuator 25. The holder 22 is provided on a distal end of the vertical movement arm 21, and the vertical movement actuator 25 is provided on a proximal end of the vertical movement arm 21. The vertical movement actuator 25 is, for example, driven by an electric motor or a fluid cylinder. The controller 8 controls an operation of the vertical movement actuator 25 along the vertical direction.

[0029]

In the processing tank 10a of the swelling processing tank 10, the holder 22 holds the substrate 4 in a vertical posture. As illustrated in FIG. 4, the holder 22

is bent in a V shape in a front view. A plurality of (at least three) substrate receivers 23 are provided on an upper surface of the holder 22. As illustrated in FIG. 5, the substrate receiver 23 has a groove having a Y shape to support and hold a lower peripheral edge of the substrate 4.

5 [0030]

When the controller 8 controls the vertical movement actuator 25 so that the vertical movement actuator 25 drives the vertical movement arm 21 along the vertical direction, thereby moving the holder 22 vertically. The substrate 4 held in a vertical posture by the holder 22 moves between the non-immersed position where the substrate 4 is lifted up from the stripping solution (that is, chemical) 6 and the immersed position where the substrate 4 is immersed in the stripping solution (that is, chemical) 6. The controller 8 controls time during which the substrate up-and-down actuator 20 keeps the substrate 4 at the immersed position, that is, swelling processing time.

10
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[0031]

20 As illustrated in FIG. 3, the articulated robot 9 includes a base 51, an articulated arm 52, the chuck 55, and a turning unit 57. A proximal end of the articulated arm 52 is fixed to a support column 59 extending perpendicularly from the base 51. A distal end of the articulated arm 52 is connected to the chuck 55 via the

25

turning unit 57. The articulated arm 52 includes a plurality of arm members, and the arm member on the proximal end is fixed to an upper end of the support column 59. The support column 59 is configured to rotate about a support shaft of the support column 59 and reciprocate perpendicularly by a drive system and a driving force transmission mechanism, not illustrated, provided inside the base 51. Therefore, the arm on the proximal end is rotatable in a horizontal plane by a rotating action of the support column 59.

10 [0032]

An arm member is attached to an arm member on its proximal side rotatably in a horizontal plane by a connecting shaft. The chuck 55 is turnably attached to the arm member on the distal end by the turning unit 57.

15 Therefore, the chuck 55 is turnable about a turning shaft of the turning unit 57.

[0033]

The plurality of arm members, the turning unit 57, and the chuck 55 are, for example, driven by drive systems provided therein with a certain rotation amount and in a certain rotation direction, with a certain turning amount and in a certain turning direction, or with a certain moving amount and in a certain moving direction. The controller 8 controls each operation of the support column 59, the plurality of arm members, the turning unit 57, and

25

the chuck 55 independently.

[0034]

As illustrated in FIGS. 6 and 7, the chuck 55 includes a locking portion 53, two claws 54, 54 provided at a distal end of the locking portion 53, and an receiving portion 56 recessed in the locking portion 53. When the locking portion 53 extends perpendicularly, the receiving portion 56 receives the substrate 4, and the two claws 54, 54 are spaced apart from each other in a width direction of the locking portion 53 to support an outer peripheral lower portion of the substrate 4. The receiving portion 56 is sized to have an outer diameter slightly larger than an outer diameter of the substrate 4. As a result, the substrate 4 can move in the receiving portion 56. When the outer peripheral lower portion of the substrate 4 is positioned at a disengagement position where the outer peripheral lower portion is not engaged with the two claws 54, 54, the substrate 4 can be disengaged from the receiving portion 56. When the outer peripheral portion of the substrate 4 is positioned at an engagement position where the outer peripheral portion is engaged with the two claws 54, 54, the substrate 4 is locked to the receiving portion 56. Therefore, the receiving portion 56 can disengageably receive the substrate 4 by adjusting positional relationship between the outer peripheral portion of the substrate 4 and the two claws

54, 54. Accordingly, the chuck 55 can disengageably chuck the substrate 4.

[0035]

The controller 8 controls an operation of the
5 chuck 55 to disengageably chuck the substrate 4. An operation of the articulated robot 9, that is, a combination of operations of the support column 59, the plurality of arm members, and the turning unit 57 can move the substrate 4 to the engagement position or the disengagement position in the
10 receiving portion 56 of the chuck 55, so that the receiving portion 56 of the chuck 55 can disengageably receive the substrate 4.

[0036]

In addition, as indicated by an arrow in FIG. 1,
15 the articulated robot 9 is movable in a horizontal direction. As a result, the articulated robot 9 can move between the carriers 2, the swelling processing tank 10, the cleaning processing tanks 5, and the drying processing tanks 7 to convey the substrate 4.

20 [0037]

A plurality of substrates 4 are placed in a horizontal posture on the carrier 2. The articulated robot 9 takes out one substrate 4 from the plurality of substrates 4 placed in a horizontal posture on the carrier 2. Then,
25 the articulated robot 9 conveys the one substrate 4 taken

out from the carrier 2 to the swelling processing tank 10,
and places the one substrate 4 in a vertical posture on an
empty holder 22. The placed one substrate 4 is held by the
holder 22. The substrate up-and-down actuator 20 moves the
5 one substrate 4 held in a vertical posture by the holder 22
downward from the non-immersed position to the immersed
position in the swelling processing tank 10. By keeping the
one substrate 4 at the immersed position for a predetermined
time, swelling processing of the one substrate 4 is performed
10 for a predetermined swelling processing time.

[0038]

When the predetermined swelling processing time
has elapsed, the substrate up-and-down actuator 20 moves the
holder 22 on which the one substrate 4 is placed upward to
15 the non-immersed position, and then the articulated robot 9
engages the one substrate 4 at the non-immersed position
with the locking portion 53 to remove the one substrate 4
from the holder 22. Then, the articulated robot 9 places
another substrate 4 different from the one substrate 4 on
20 the holder 22 at the non-immersed position. In such a way,
resist removal processing is individually performed for each
substrate 4.

[0039]

The articulated robot 9 conveys the substrate 4
25 subjected to the swelling processing from the swelling

processing tank 10 to the cleaning processing tank 5. In the cleaning processing tank 5, cleaning processing (so-called "rinse processing") to remove residues remaining on a surface of the substrate 4 is performed for the substrate 4 which was subjected to the swelling processing. The cleaning processing tank 5 includes a two-fluid nozzle. From the two-fluid nozzle, a rinse fluid containing a pressurized gas (for example, nitrogen gas) and a cleaning liquid (for example, pure water) is sprayed onto the surface of the substrate 4. When the rinse fluid is sprayed onto the surface of the substrate 4, residues remaining on the surface of the substrate 4 are removed from the surface of the substrate 4. As a result, the substrate 4 is subjected to the cleaning processing. Note that a backup plate may be disposed on a back surface of the substrate 4, in particular, when the substrate 4 is thin. The back surface of the substrate 4 can also be cleaned using a substrate back surface center nozzle.

[0040]

The articulated robot 9 conveys the substrate 4, which was subjected to the cleaning processing, from the cleaning processing tank 5 to the drying processing tank 7. In the drying processing tank 7, for example, so-called spin drying is performed to scatter the rinse fluid adhering to the substrate 4 using centrifugal force by rotating the

substrate 4 at a high speed, thereby drying the substrate 4.
[0041]

The articulated robot 9 conveys the substrate 4, which was subjected to drying processing, from the drying
5 processing tank 7 to the carrier 2. In the carrier 2, the substrate 4 is placed in a horizontal posture, for example. By placing the substrate 4 on the carrier 2, a series of processing for the substrate 4 in the liquid chemical processing device 1 is completed. The controller 8 controls
10 the operations of the liquid chemical processing device 1 so as to repeatedly perform the same operations for each of other substrates 4, including the resist removal processing for the plurality of substrates 4 one by one (that is, in a single wafer manner). Therefore, the swelling processing
15 time of the substrates 4 can be individually set, so that it is possible to decrease a difference in the swelling processing time for each substrate 4. Accordingly, it is possible to suppress variation in photoresist removal for each substrate 4.

20 [0042]

According to the liquid chemical processing device 1 of the first embodiment, the substrates 4 held by the holders 22 individually and vertically move between the immersed position and the non-immersed position, and are
25 subjected to the resist removal processing in a single wafer

manner. Accordingly, it is possible to suppress variation in resist removal for each substrate 4.

[0043]

[Second embodiment]

5 The liquid chemical processing device 1 according to a second embodiment will be described with reference to FIG. 9. FIG. 9 is a plan view illustrating the swelling processing system 3 in the liquid chemical processing device 1 according to the second embodiment.

10 Other than characteristic portions, configurations of the liquid chemical processing device 1 according to the second embodiment are the same as those of the liquid chemical processing device 1 according to the first embodiment. Accordingly, the characteristic portions of the liquid

15 chemical processing device 1 according to the second embodiment will be mainly described.

[0044]

As illustrated in FIG. 9, the substrate up-and-down actuators 20 are provided in a staggered arrangement

20 with respect to the swelling processing tank 10 of the liquid chemical processing device 1. Although the vertical movement actuators 25 are provided in a staggered arrangement, the holders 22 are arranged in a row spaced apart from each other along the longitudinal direction (that is, lateral

25 direction) of the processing tank 10a by adjusting horizontal

lengths of the vertical movement arms 21. Therefore, the substrates 4 held by the holders 22 are also positioned in a row spaced apart from each other along the longitudinal direction (that is, lateral direction) of the processing tank 10a. The vertical movement actuators 25, which require space in the lateral direction, are alternately set back, and adjacent vertical movement arms 21 are disposed close to each other and adjacent holders 22 are disposed close to each other. Accordingly, intervals between adjacent substrates 4 can be shortened.

[0045]

With such a configuration, it is possible to shorten the intervals between adjacent substrates 4, save the space for the swelling processing tank 10 (for example, saving about 20% as compared with the swelling processing tank 10 illustrated in FIG. 8), and reduce the stripping solution (that is, chemical) 6 used in the swelling processing tank 10.

[0046]

[Third embodiment]

The liquid chemical processing device 1 according to a third embodiment will be described with reference to FIGS. 10 and 11. FIG. 10 is a plan view illustrating the liquid chemical processing device 1 according to the third embodiment. FIG. 11 is a plan view

illustrating the swelling processing tank 10 in the liquid chemical processing device 1 illustrated in FIG. 10. Other than characteristic portions, configurations of the liquid chemical processing device 1 according to the third embodiment are the same as those of the liquid chemical processing device 1 according to the first embodiment. Accordingly, the characteristic portions of the liquid chemical processing device 1 according to the third embodiment will be mainly described.

10 [0047]

As illustrated in FIGS. 10 and 11, the swelling processing tank 10 is fan-shaped in a plan view, and the articulated robot 9 is disposed at a center of the fan shape. The substrate up-and-down actuators 20 are provided along an outer arc of the swelling processing tank 10. The substrate up-and-down actuators 20, which require space in the lateral direction, are disposed on a side of the outer arc of the fan shape, so that adjacent vertical movement arms and adjacent holders 22 are disposed close to each other. Accordingly, intervals between adjacent substrates 4 can be decreased.

[0048]

With such a configuration, it is possible to save the space for the swelling processing tank 10 (for example, saving about 44% as compared with the swelling processing

tank 10 illustrated in FIG. 8), reduce the stripping solution (that is, chemical) 6 used in the swelling processing tank 10, and reduce a rotation radius of the articulated robot 9.

[0049]

5 [Fourth embodiment]

The liquid chemical processing device 1 according to a fourth embodiment will be described with reference to FIG. 12. FIG. 12 is a plan view illustrating the swelling processing tank 10 in the liquid chemical processing device 1 according to the fourth embodiment.

10 Other than characteristic portions, configurations of the liquid chemical processing device 1 according to the fourth embodiment are the same as those of the liquid chemical processing device 1 according to the third embodiment.

15 Accordingly, the characteristic portions of the liquid chemical processing device 1 according to the fourth embodiment will be mainly described.

[0050]

As illustrated in FIG. 12, the substrate up-and-down actuators 20 are provided in a staggered arrangement with respect to the swelling processing tank 10 having a fan shape in a plan view. Although the vertical movement actuators 25 are provided in a staggered arrangement, the holders 22 are arranged in a row spaced apart from each other

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25 along a circumferential direction of the processing tank 10a

by adjusting horizontal lengths of the vertical movement arms 21. Therefore, the substrates 4 held by the holders 22 are positioned in a row spaced apart from each other along the circumferential direction of the processing tank 10a.

5 The vertical movement actuators 25, which require space in the circumferential direction, are alternately set back, and adjacent vertical movement arms 21 are disposed close to each other and adjacent holders 22 are disposed close to each other. Accordingly, intervals between adjacent
10 substrates 4 can be decreased.

[0051]

With such a configuration, it is possible to shorten the intervals between adjacent substrates 4, save the space for the swelling processing tank 10, and reduce
15 the stripping solution (that is, chemical) 6 used in the swelling processing tank 10.

[0052]

Specific embodiments of the present invention have been described. However, the present invention is not
20 limited to the above embodiments, and can be implemented with various modifications made within the scope of the present invention.

[0053]

In the above embodiments, the substrates 4 are
25 placed in a horizontal posture on the carriers 2. However,

the substrates 4 may be placed in a vertical posture on the carriers 2.

[0054]

In the above embodiments, the rinse fluid
5 sprayed from the two-fluid nozzle in the cleaning processing tank 5 includes nitrogen as the pressurized gas and pure water as the cleaning liquid. However, an inert gas or the like may be used as the pressurized gas, and chemicals other than organic solvent may be used as the cleaning liquid.

10 [0055]

In the above embodiments, the liquid chemical processing device 1 includes one swelling processing tank 10, two cleaning processing tanks 5, 5, and two drying processing tanks 7, 7. Not limited thereto, the number of
15 tanks of the liquid chemical processing device 1 can be increased or decreased.

[0056]

In the above embodiments, a conveyance device to convey the substrates 4 is the articulated robot 9. However,
20 other various conveyance units can be used as the conveyance device.

[0057]

In the above embodiments, the lift-off processing are performed for circuit patterns of metal films
25 formed on the substrates 4. However, the liquid chemical

processing device 1 according to the present invention can also be applied to resist removal processing for patterns of various films formed on various substrates 4 in manufacturing, for example, flat panel display (that is, FPD) substrates, surface acoustic wave (that is, SAW) devices, micro-electro mechanical systems (that is, MEMs), hard disks, or the like.
[0058]

The present invention and embodiments are summarized as follows.

10 [0059]

The liquid chemical processing device 1 according to one aspect of the present invention includes:

the processing tank 10a in which resist removal processing is performed by immersing the substrates 4 in the
15 chemical 6;

the plurality of holders 22 configured to hold the substrates 4 in a vertical posture;

the vertical drivers 20 configured to individually and vertically drive the holders 22; and

20 the chuck 53 configured to disengageably chuck the substrates 4,

wherein the vertical drivers 20 are configured to individually and vertically move the holders 22 between the immersed position where the substrates 4 are immersed in
25 the chemical 6 and the non-immersed position where the

substrates 4 are lifted up from the chemical 6, and the substrates 4 held by the holders 22 are subjected to the resist removal processing in a single wafer manner.

[0060]

5 With such a configuration, the substrates 4 held by the holders 22 individually and vertically move between the immersed position and the non-immersed position, and are subjected to the resist removal processing in a single wafer manner. Accordingly, it is possible to suppress variation
10 in resist removal for each substrate 4.

[0061]

 Further, in the liquid chemical processing device 1 according to one embodiment, the ultrasonic generator 17 is disposed at the bottom of the processing
15 tank 10a.

[0062]

 According to the above embodiment, stripping of the coating material from the substrates 4 is promoted, and the coating material stripped off from the substrates 4 is
20 pulverized, so that the sludge generated by the pulverization easily flows toward downstream.

[0063]

 Further, in the liquid chemical processing device 1 according to one embodiment, the nozzle 14 is
25 disposed at the upper portion of the processing tank 10a,

the nozzles 14 being configured to eject the chemical 6 downward toward the substrates 4.

[0064]

According to the above embodiment, the stripped
5 coating material is prevented from readhering to the substrates 4, so that the generated sludge is easily recovered.

[0065]

Further, in the liquid chemical processing
10 device 1 according to one embodiment, the processing tank 10a communicates with the storage tank 10b adjacent to the processing tank 10a through the communication port 15 provided in the bottom of the communication side-wall 11 of the processing tank 10a.

15 [0066]

According to the above embodiment, the chemical
6 in the processing tank 10a flows into the storage tank 10b as downflow. Accordingly, it is possible to prevent the stripped coating material from readhering to the substrates
20 4.

[0067]

Further, in the liquid chemical processing
device 1 according to one embodiment, the discharge tank 10c is disposed adjacent to the storage tank 10b to store the
25 chemical 6 that overflows from the storage tank 10b; and the

circulation path 40 is provided between the nozzles 14 and the discharge tank 10c to allow the chemical 6 to circulate.

[0068]

According to the above embodiment, the organic
5 solvent and the metal contained in the used chemical 6 can be reused, so that the running costs of the liquid chemical processing device 1 can be reduced.

[0069]

Further, in the liquid chemical processing
10 device 1 according to one embodiment, the filtering systems 31, 48, and 49 in which the recovery target size of the sludge contained in the chemical 6 is reduced stepwise are provided in the circulation path 40.

[0070]

15 According to the above embodiment, it is possible to reduce the replacement frequency of expensive filter elements, suppress downtime of the liquid chemical processing device 1, and increase the production efficiency.

[0071]

20 Further, in the liquid chemical processing device 1 according to one embodiment, the stagnation prevention portion 16 is provided at the bottom of the storage tank 10b on the opposite side of the communication port 15.

25 [0072]

According to the above embodiment, it is possible to prevent sludge from accumulating at the corner where the bottom of the storage tank 10b and the overflow side-wall 12 intersect with each other.

5 [0073]

The liquid chemical processing device 1 according to one embodiment further includes the controller 8 configured to control each of the vertical drivers 20 and the chuck 55,

10 wherein the controller 8 is configured to perform the resist removal processing individually for each of the substrates 4, the resist removal processing including:

placing one of the substrates 4 on the holder 22 at the non-immersed position;

15 moving the holder 22 holding the substrate 4 downward to the immersed position;

keeping the one substrate 4 at the immersed position for a predetermined time;

20 moving the holder 22 holding the substrate 4 upward to the non-immersed position;

chucking the substrate 4 at the non-immersed position by the chuck 55 and removing the substrate 4 from the holder 22; and

25 placing another of the substrates 4 different from the substrate 4 on the holder 22 at the non-immersed

position.

[0074]

According to the above embodiment, the swelling processing time of the substrates 4 can be individually managed, so that it is possible to decrease a difference in the swelling processing time for each substrate 4. Accordingly, it is possible to suppress variation in resist removal for each substrate 4.

[0075]

10 Further, in the liquid chemical processing device 1 according to one embodiment, the vertical drivers 20 are provided in a staggered arrangement with respect to the processing tank 10a.

[0076]

15 According to the above embodiment, it is possible to shorten the intervals between adjacent substrates 4, save the space for the processing tank 10a, and reduce the chemical 6 used in the processing tank 10a.

[0077]

20 Further, in the liquid chemical processing device 1 according to one embodiment, the processing tank 10a is fan-shaped in a plan view, and the vertical drivers 20 are provided along the outer arc of the processing tank 10a.

25 [0078]

According to the above embodiment, it is possible to save the space for the processing tank 10a and reduce the chemical 6 used in the processing tank 10a.

5 Reference Numerals

[0079]

	1	liquid chemical processing device
	2	carrier
	3	swelling processing system
10	4	substrate
	5	cleaning processing tank
	6	stripping solution (chemical)
	7	drying processing tank
	8	controller
15	9	articulated robot
	10	swelling processing tank
	10a	processing tank
	10b	storage tank
	10c	discharge tank
20	11	communication side-wall
	12	overflow side-wall
	14	nozzle
	15	communication port
	16	stagnation prevention portion
25	17	ultrasonic generator

	20	substrate up-and-down actuator (vertical driver)
	21	vertical movement arm
	22	holder
5	23	substrate receiver
	25	vertical movement actuator
	30	sludge recovery tank (sludge recovery unit)
	31	mesh filter (filtering system)
10	32	coarse mesh basket
	33	intermediate mesh basket
	34	fine mesh basket
	36	filter take-out portion
	37	exhaust unit
15	40	circulation path
	41	pipe
	42	pipe
	43	pipe
	44	pipe
20	45	pipe
	46	valve
	47	circulation pump
	48	liquid cyclone (filtering system)
	49	chemical filter (filtering system)
25	51	base

	52	articulated arm
	53	locking portion
	54	claw
	55	chuck
5	56	receiving portion
	57	turning unit
	59	support column

CLAIMS

1. A liquid chemical processing device comprising:

5 a processing tank in which resist removal processing is performed by immersing substrates in a chemical;

a plurality of holders configured to hold the substrates in a vertical posture;

10 vertical drivers configured to individually and vertically drive the holders; and

a chuck configured to disengageably chuck the substrates,

wherein the vertical drivers are configured to
15 individually and vertically move the holders between an immersed position where the substrates are immersed in the chemical and a non-immersed position where the substrates are lifted up from the chemical, and the substrates held by the holders are subjected to the resist removal processing
20 in a single wafer manner.

2. The liquid chemical processing device according to claim 1, wherein an ultrasonic generator is disposed at a bottom of the processing tank.

25

3. The liquid chemical processing device according to claim 1 or 2, wherein a nozzle is disposed at an upper portion of the processing tank, the nozzle being configured to eject the chemical downward toward the
5 substrates.

4. The liquid chemical processing device according to claim 3, wherein the processing tank communicates with a storage tank adjacent to the processing
10 tank through a communication port provided in a bottom of a communication side-wall of the processing tank.

5. The liquid chemical processing device according to claim 4, wherein a discharge tank is disposed
15 adjacent to the storage tank to store the chemical that overflows from the storage tank, and a circulation path is provided between the nozzle and the discharge tank to allow the chemical to circulate.

20 6. The liquid chemical processing device according to claim 5, wherein a filtering system in which recovery target size of sludge contained in the chemical is reduced stepwise is provided in the circulation path.

25 7. The liquid chemical processing device

according to any one of claims 4 to 6, wherein a stagnation prevention portion is provided at a bottom of the storage tank on an opposite side of the communication port.

5 8. The liquid chemical processing device according to any one of claims 1 to 7, further comprising a controller configured to control each of the vertical drivers and the chuck,

 wherein the controller is configured to perform
10 the resist removal processing individually for each of the substrates, the resist removal processing including:

 placing one of the substrates on the holder at the non-immersed position;

 moving the holder holding the substrate downward
15 to the immersed position;

 keeping the substrate at the immersed position for a predetermined time;

 moving the holder holding the substrate upward to the non-immersed position;

20 chucking the substrate at the non-immersed position by the chuck and removing the substrate from the holder; and

 placing another of the substrates different from the substrate on the holder at the non-immersed position.

25

9. The liquid chemical processing device according to any one of claims 1 to 8, wherein the vertical drivers are provided in a staggered arrangement with respect to the processing tank.

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10. The liquid chemical processing device according to any one of claims 1 to 9, wherein the processing tank is fan-shaped in a plan view, and the vertical drivers are provided along an outer arc of the processing tank.

10